

MRT 6/7/00

Amend  
6/6  
6/28/00  
BCL/mme

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of

MORIFUJI

Appln. No. 09/493,063

Filed: January 28, 2000

Title: SEMICONDUCTOR DEVICE AND METHOD  
OF MANUFACTURING THE SAME

\* \* \* \* \*

June 7, 2000

PRELIMINARY AMENDMENT

Hon. Commissioner of Patents  
and Trademarks  
Washington, DC 20231

Sir:

Before initial examination, please preliminarily amend the above-identified  
application as follows:

IN THE ABSTRACT:

Lines 3 and 4, delete "decreases the substrate resistance" and insert --suppresses the  
influence of the substrate resistance--.

IN THE SPECIFICATION:

Page 2, line 31, delete "heat" and insert --thermal--.

Page 3, line 21, delete "the substrate resistance is decreased" and insert --the  
influence of the substrate resistance is suppressed--.

line 22, delete "heat" and insert --thermal--.